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TITLE: GAS INTRODUCING APPARATUS FOR  
REACTION CHAMBER  
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ABSTRACT:

PURPOSE: To uniform a thin film formed on a wafer without rotating the susceptor, by stirring entering gas with a variable speed impeller, to regulate the flow rate and path of the gas.

CONSTITUTION: On the top of a reaction chamber 1, an impeller chamber 2 is provided, on the top of which an output shaft 4 of a rotary introducing member 3 is mounted vertically. At the lower end of the output shaft 4, an impeller 5 is fixed. Gas is introduced as shown by the arrows 9, 10 while the motor is

started and thus the output shaft 4 of the rotary introducing member 3 is rotated at a given rotating speed. At this time, the entering gas is blown toward the wafer 7 as shown by the arrows 14, 15. In this case, by varying the rotating speed of the impeller 5, the nature of the whirled flow can be varied, so that the gas flow contacting the upper face of the wafer can be uniformed to uniform a thin film formed on the wafer.

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